

L Number	Hits	Search Text	DB	Time stamp
1	325	((stress or stresses or stressed) and ((mask or photomask or reticle) and (reflect or reflection or reflectance or reflective))) and (nmrms or rms)	USPAT; US-PGPUB; EPO; JPO	2003/06/27 14:48
2	176	((stress or stresses or stressed) and ((mask or photomask or reticle) and (reflect or reflection or reflectance or reflective))) and (euv or (enhanced adj ultraviolet) or duv)	USPAT; US-PGPUB; EPO; JPO	2003/06/27 14:20
3	6085	430/5.ccls.	USPAT; US-PGPUB; EPO; JPO	2003/06/27 14:20
4	1132	378/34-35.ccls.	USPAT; US-PGPUB; EPO; JPO	2003/06/27 14:21
5	33	430/5.ccls. and (((stress or stresses or stressed) and ((mask or photomask or reticle) and (reflect or reflection or reflectance or reflective))) and (euv or (enhanced adj ultraviolet) or duv))	USPAT; US-PGPUB; EPO; JPO	2003/06/27 14:22
6	18	378/34-35.ccls. and (((stress or stresses or stressed) and ((mask or photomask or reticle) and (reflect or reflection or reflectance or reflective))) and (euv or (enhanced adj ultraviolet) or duv))	USPAT; US-PGPUB; EPO; JPO	2003/06/27 14:47
7	63130	warp or warping	USPAT; US-PGPUB; EPO; JPO	2003/06/27 14:47
8	292657	mask or photomask or reticle	USPAT; US-PGPUB; EPO; JPO	2003/06/27 14:47
9	473652	reflect or reflection or reflectance or reflective	USPAT; US-PGPUB; EPO; JPO	2003/06/27 14:48
10	33754	nmrms or rms	USPAT; US-PGPUB; EPO; JPO	2003/06/27 14:48
11	894697	flatness or flat	USPAT; US-PGPUB; EPO; JPO	2003/06/27 14:48
12	3293	euv or (enhanced adj ultraviolet) or duv	USPAT; US-PGPUB; EPO; JPO	2003/06/27 14:48
13	51827	((mask or photomask or reticle) and (reflect or reflection or reflectance or reflective)	USPAT; US-PGPUB; EPO; JPO	2003/06/27 14:48
14	1258	(warp or warping) and ((mask or photomask or reticle) and (reflect or reflection or reflectance or reflective))	USPAT; US-PGPUB; EPO; JPO	2003/06/27 14:48
15	133	(nmrms or rms) and ((warp or warping) and ((mask or photomask or reticle) and (reflect or reflection or reflectance or reflective)))	USPAT; US-PGPUB; EPO; JPO	2003/06/27 14:48
16	442035	stress or stresses or stressed	USPAT; US-PGPUB; EPO; JPO	2003/06/27 14:49
17	6897	((mask or photomask or reticle) and (reflect or reflection or reflectance or reflective)) and (stress or stresses or stressed)	USPAT; US-PGPUB; EPO; JPO	2003/06/27 14:49
18	34	((mask or photomask or reticle) and (reflect or reflection or reflectance or reflective)) and (stress or stresses or stressed)) and ((nmrms or rms) and ((warp or warping) and ((mask or photomask or reticle) and (reflect or reflection or reflectance or reflective))))	USPAT; US-PGPUB; EPO; JPO	2003/06/27 14:51

19	444	((mask or photomask or reticle) and (reflect or reflection or reflectance or reflective)) and (stress or stresses or stressed)) and ((warp or warping) and ((mask or photomask or reticle) and (reflect or reflection or reflectance or reflective)))	USPAT; US-PGPUB; EPO; JPO	2003/06/27 14:51
20	6931	430/5.ccls. or 378/34-35.ccls.	USPAT; US-PGPUB; EPO; JPO	2003/06/27 14:51
21	21	((((mask or photomask or reticle) and (reflect or reflection or reflectance or reflective)) and (stress or stresses or stressed)) and ((warp or warping) and ((mask or photomask or reticle) and (reflect or reflection or reflectance or reflective)))) and (430/5.ccls. or 378/34-35.ccls.)	USPAT; US-PGPUB; EPO; JPO	2003/06/27 14:53
22	2716	buffer with (stress or stresses or stressed)	USPAT; US-PGPUB; EPO; JPO	2003/06/27 14:53
23	10	(430/5.ccls. or 378/34-35.ccls.) and (buffer with (stress or stresses or stressed))	USPAT; US-PGPUB; EPO; JPO	2003/06/27 14:56